

ABSTRACT

An object of the invention is to provide a method for manufacturing a polishing pad containing substantially
5 spherical cells and having high thickness accuracy. The invention is directed to a method for manufacturing a polishing pad, comprising the steps of: preparing a cell-dispersed urethane composition by a mechanical foaming method; continuously discharging the cell-dispersed
10 urethane composition from a single discharge port to a substantially central portion in the width direction of a face material A, while feeding the face material A; laminating a face material B on the cell-dispersed urethane composition; then uniformly adjusting the thickness of the
15 cell-dispersed urethane composition by thickness adjusting means; curing the cell-dispersed urethane composition with the thickness adjusted in the preceding step without applying any additional load to the composition so that a polishing sheet including a polyurethane foam is formed;
20 and cutting the polishing sheet.